

Notice of References Cited	Application/Control No. 09/418,818	Applicant(s)/Patent Under Reexamination CHEUNG ET AL.	
	Examiner Rudy Zervigon	Art Unit 1763	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,300,460	04-1994	Collins et al.	438/712
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
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	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	J. Batelly and E. Tierney, "Low-temperature deposition of high-quality silicon dioxide by plasma-enhanced chemical vapor deposition" J.Appl.Phys. 60(9), 1 November 1986, pp.3136-3145
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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